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ATTORNEY DOCKET NO.: AGX-14-CPA

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of Gat et al.

Serial No.: 09/226,396

Examiner: NGUYEN, KIET

Filed: January 6, 1999

Art Unit: 2881

For: HEATING DEVICE FOR

HEATING SEMICONDUCTOR

WAFERS IN THERMAL PROCESSING CHAMBERS

Commissioner for Patents

Box AF

Washington, D.C. 20231

AMENDMENT AFTER FINAL

Dear Sir:

In response to the Office Action dated June 11, 2002, please amend the above-captioned application as follows:

IN THE CLAIMS

Please cancel claims 34 and 57.

Please amend claims 32, 37 and 51 to read as follows (marked changes included as

Appendix A):

32. An apparatus for heat treating semiconductor wafers comprising:

a thermal processing chamber adapted to contain a semiconductor wafer; and

a heating device in communication with said thermal processing chamber for

heating a semiconductor wafer in said chamber, said heating device comprising:

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